

Notice of References Cited	Application/Control No. 10/502,232	Applicant(s)/Patent Under Reexamination EAL H. LEE	
	Examiner Chandra Chaudhari	Art Unit 2891	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-5,245,207	09-1993	Mikoshiba et al.	257/392
*	B	US-6,156,647	12-2000	Hogan, Barry	438/653
*	C	US-6,204,171	03-2001	Hu, Yongjun	257/E21.584
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Wolf, "Silicon Processing for the VLSI Era", vol. 2, pages 189-193.
	V	Sakamoto, "Preparation and microstructure of reactively sputtered Ti(1-x)Zr(x)N films", Thin Solid Films 228(1993), pages 169-172.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.